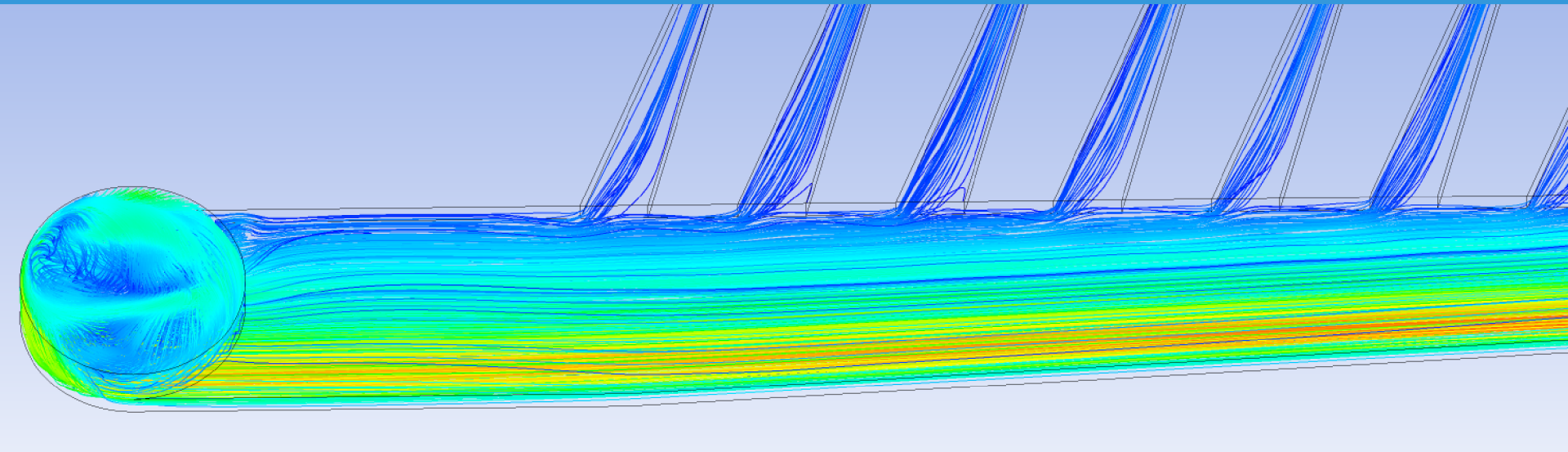


Micro-channel Cooling For Silicon Detectors



Nils Flaschel, Dario Ariza, Sergio Díez , Marta Gerboles,
Ingrid-Maria Gregor, Xavier Jorda, Roser Mas, Andreas
Mussgiller, David Quirion, Kerstin Tackmann, Miguel Ullan
Micro-channel Cooling
Strasbourg, 31.10.2016

➤ Motivation For A Micro-channel Cooling System

- Improving The Current Cooling Design

➤ Micro-Channels

- Fabrication
- Layout
- Prototype

➤ Test Stand

➤ Flow Study

➤ Thermal Study

➤ Summary & Future Steps

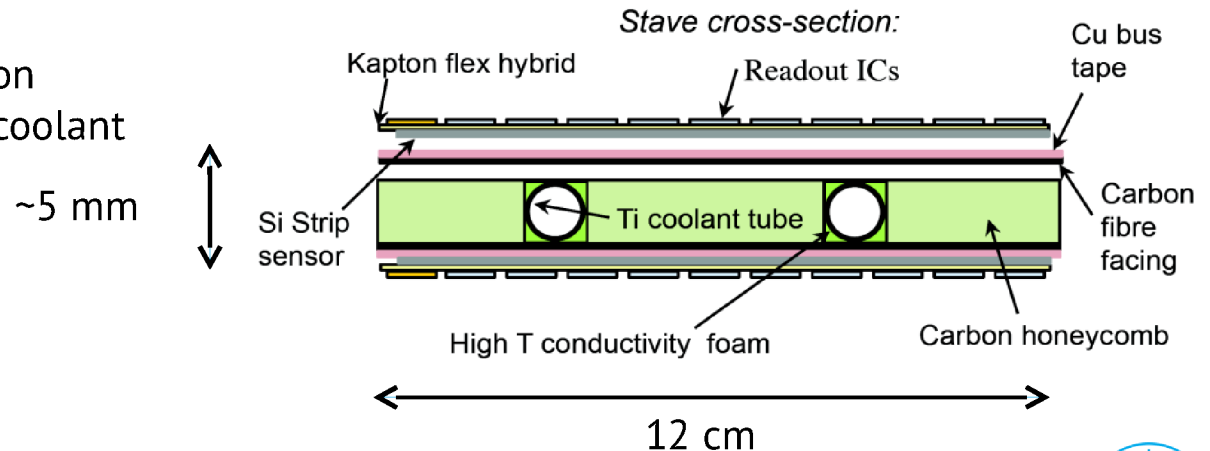


Motivation For A Micro-channel Cooling System

- Read-out electronics inside the detector produce significant heat
 - Risk of thermal runaway
 - Leakage current due to radiation damage resulting in increasing electronic noise during data taking
- Particles lose energy passing material in the detector via multiple scattering
 - ➡ save material

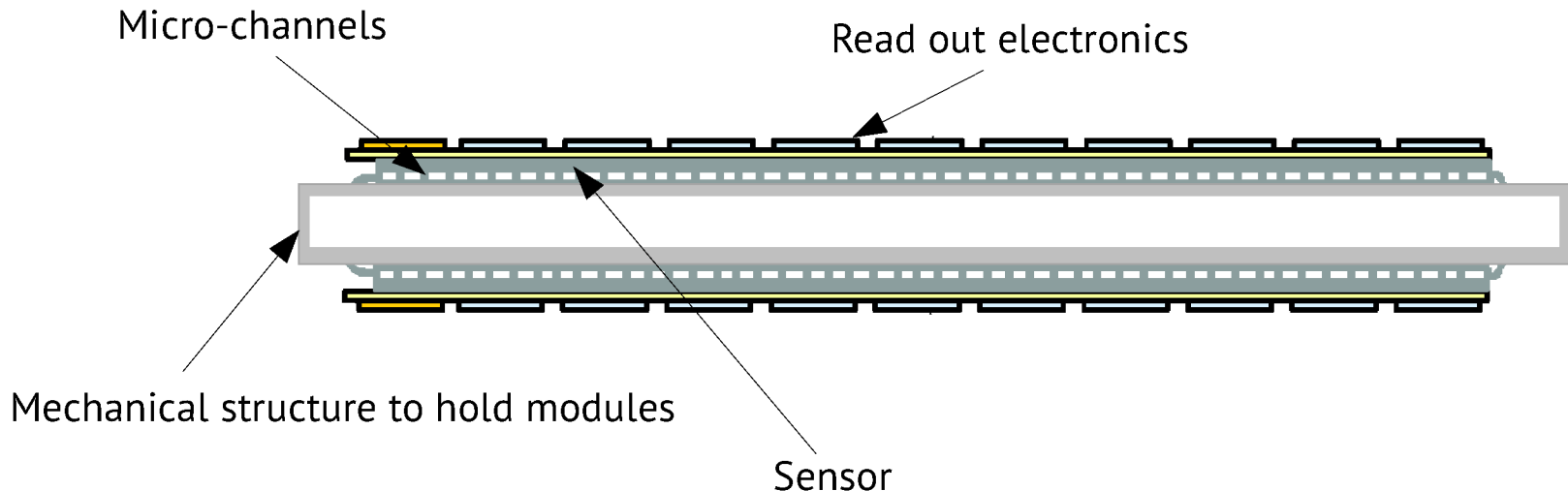
➤ The ATLAS Inner Detector as an example

- CTE mismatch
- Cooling system based on titanium pipes for the coolant



Improving The Cooling Design

- What if we could include the cooling into the sensor?
 - CTE match
 - Saves material and cooling power
 - Micro-channel technology is a strong candidate
- Project of DESY/CNM considered as generic R&D
- Other projects are employing this technology (LHCb, Na62, ILC etc)



Micro-channel Fabrication

Start with blank wafer



Use lithographic techniques



DRIE for the channels



Anodic Bonding

Silicon-Pyrex

Temperature and electrostatic field

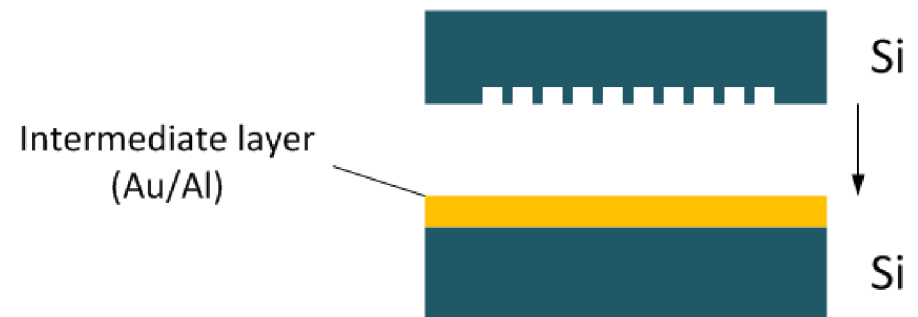
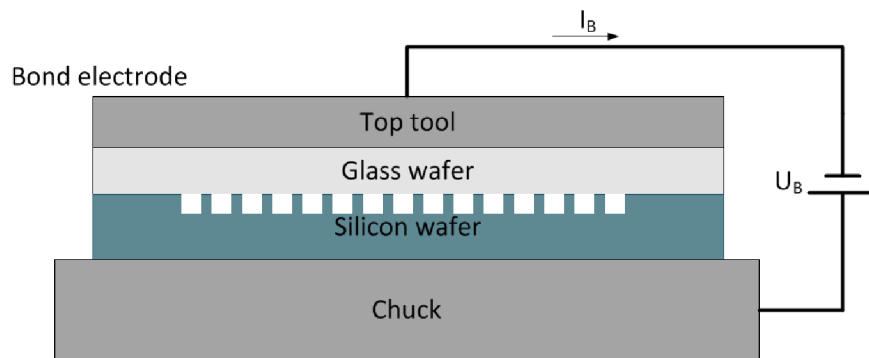
No intermediate layer

Eutectic Bonding

Silicon-silicon (intermediate metal layer)

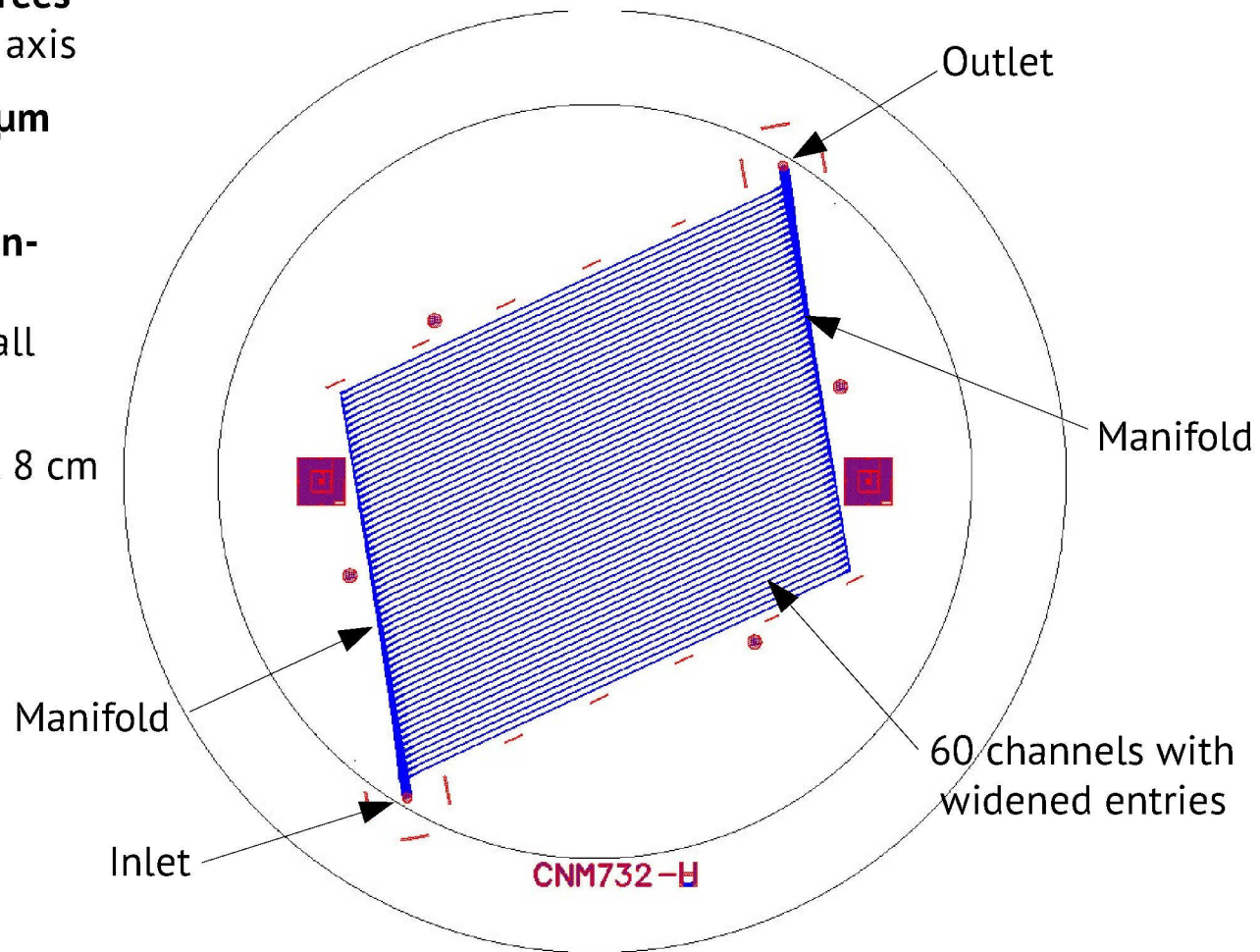
Temperature and mechanical pressure

e.g. metal sputtered or CVD

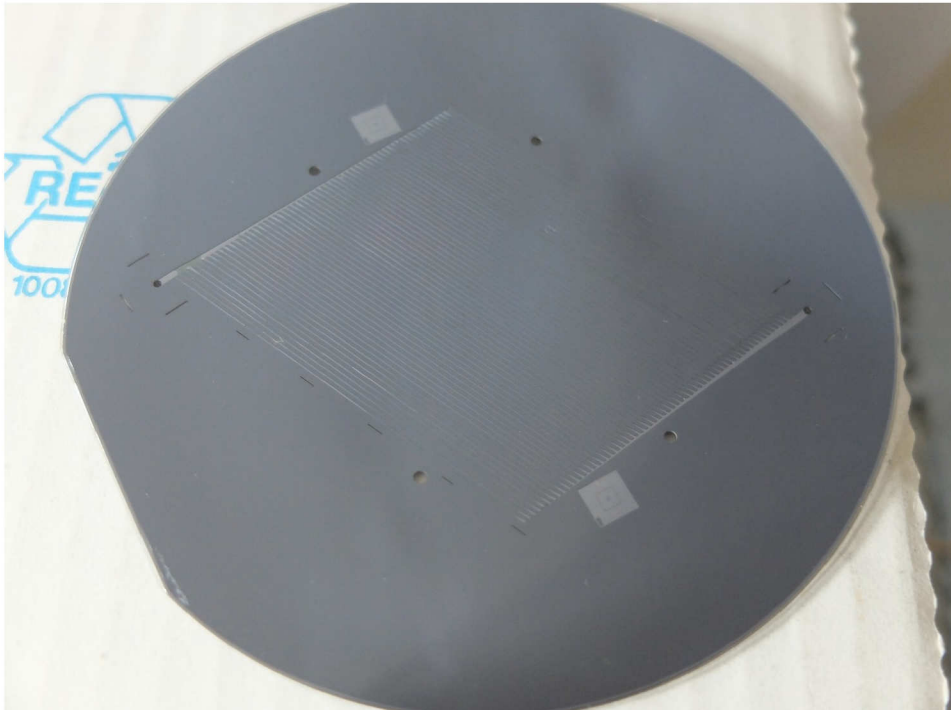


The Layout Of The Micro-channel Structure

- Channels are **rotated 15 degrees** with respect to the manifold axis
- Channels are **100 μm x 100 μm** wide and high
- Manifolds are **shaped in a non-linear way** to provide a homogeneous flow through all channels
- Distance from Inlet to Outlet 8 cm

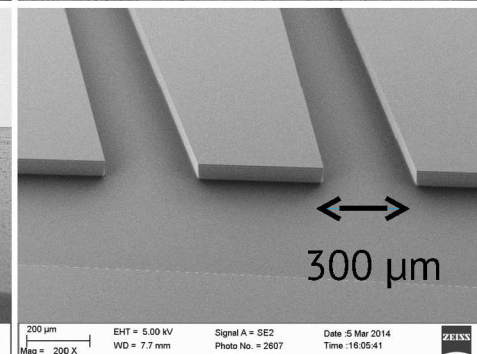
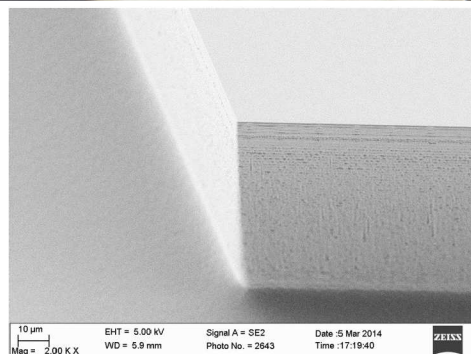
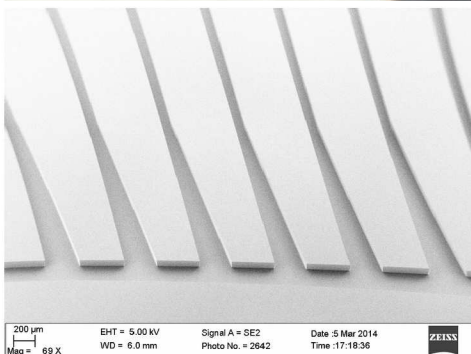
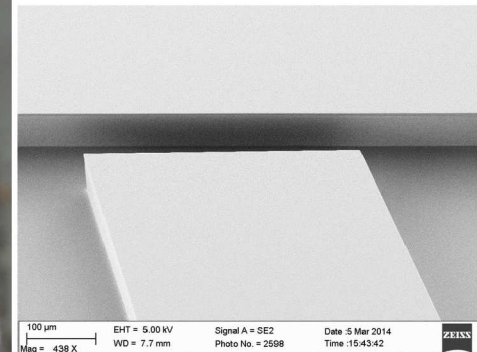


Prototype



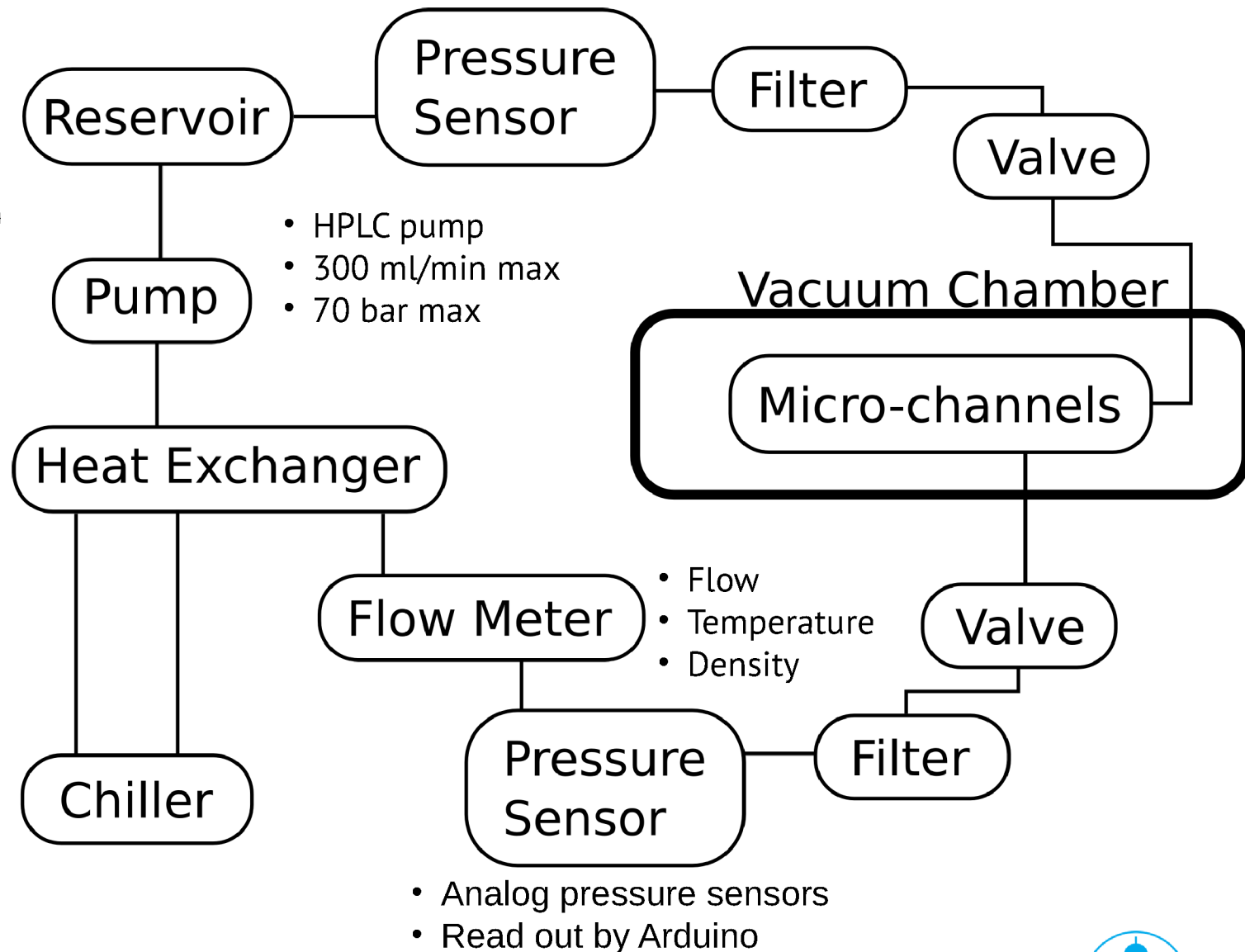
- Samples with Pyrex or silicon top
- Silicon thickness: 300-500 μm
- Pyrex/silicon thickness: 500 μm
- Pyrex useful to see clogged channels

SEM pictures



The Test Stand For The Measurements On The Prototype

- 3M HFE 7100 (Hydrofluoroether)
- Low viscosity at low temperatures 0.7 cSt
- At ~20 C for first studies

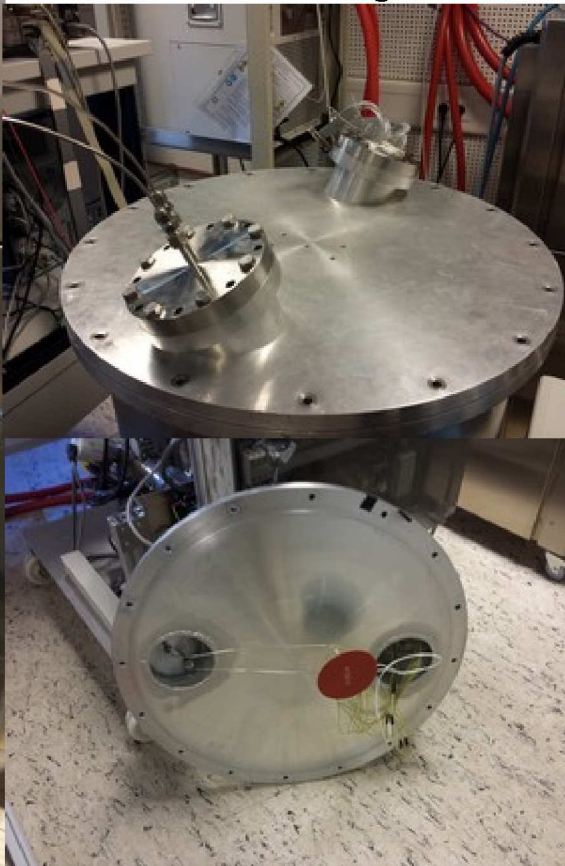


The Setup



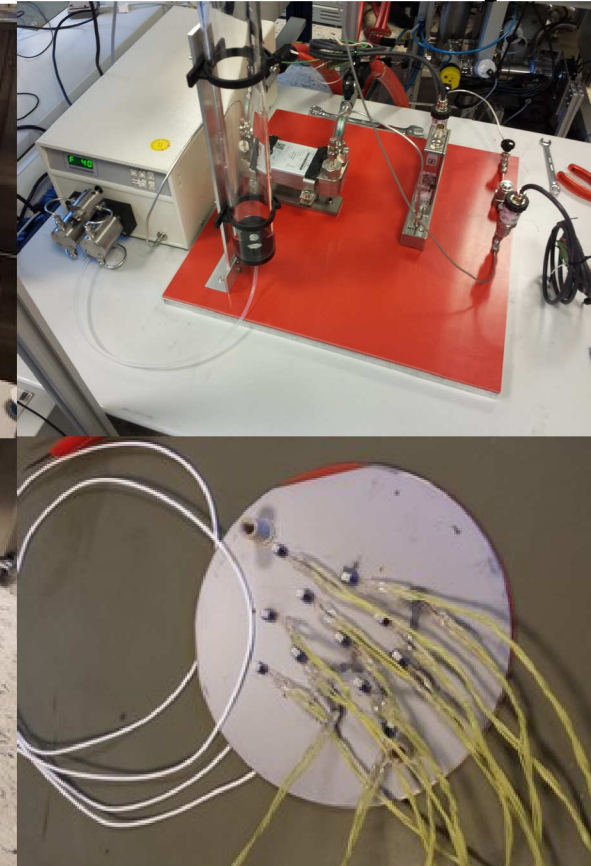
Vacuum chamber

Top of the lid
with feedthrough



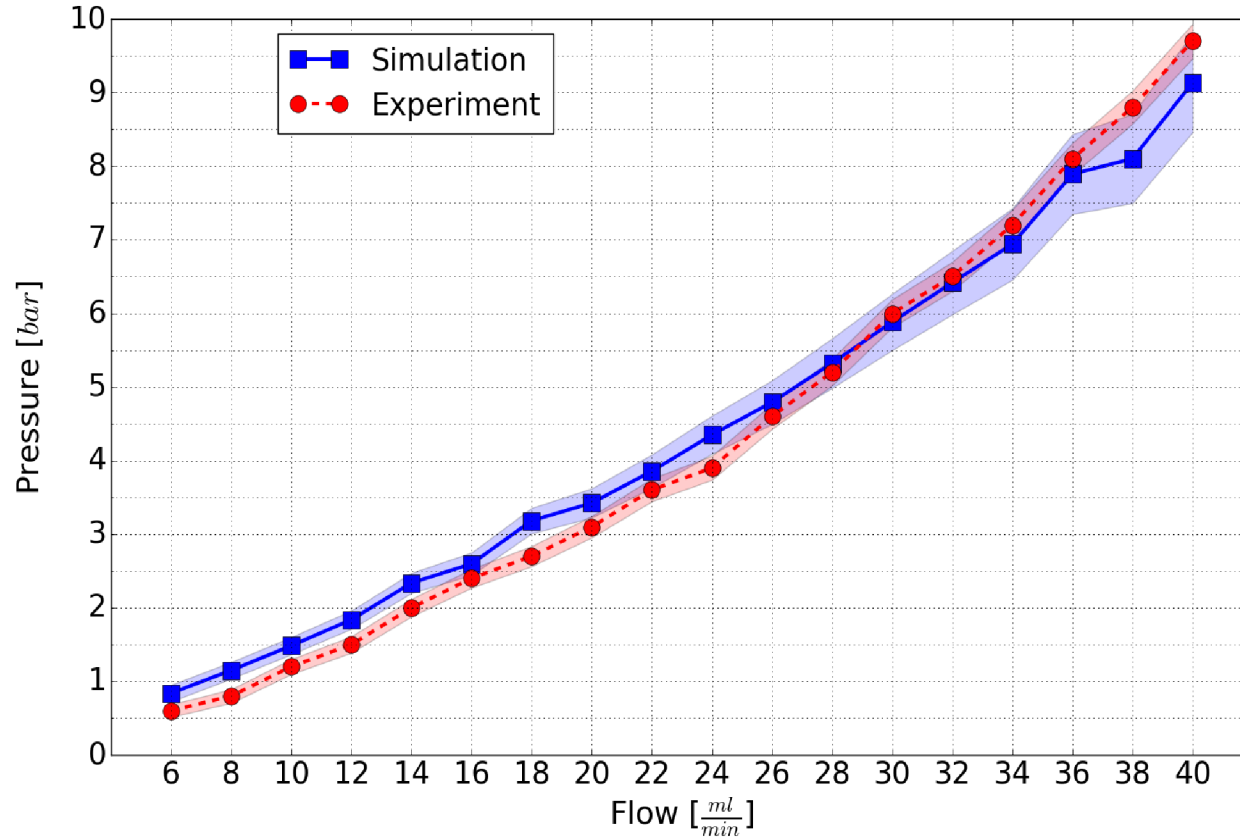
Bottom of the lid
with micro-channels

Pump, flow meter, pressure
sensors and heat exchanger



Temperature sensors arranged
on wafer with 4" heater
on the backside

Flow Measurements Versus Simulation



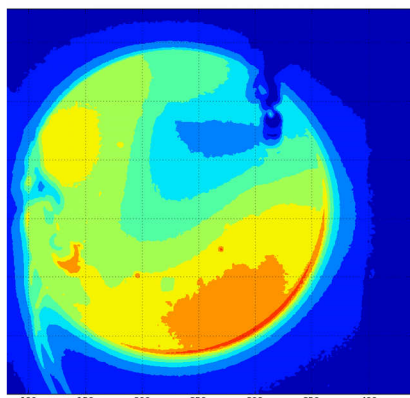
- Good agreement
- Fluctuations in the simulation grow towards higher flow rates

- Fluid is HFE at ~ 22 °C
- Error in simulation obtained through mesh refinement

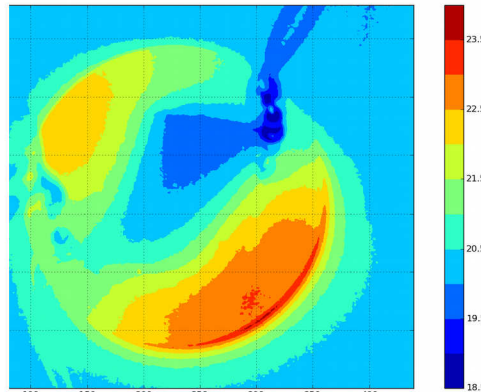
Temperature Distribution

Heater set to 2.5 W

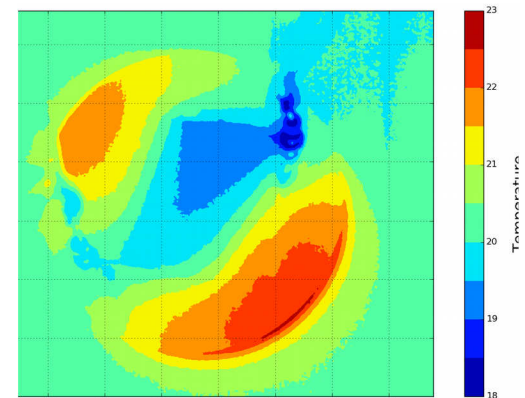
Infrared camera (in air)



10 ml/min



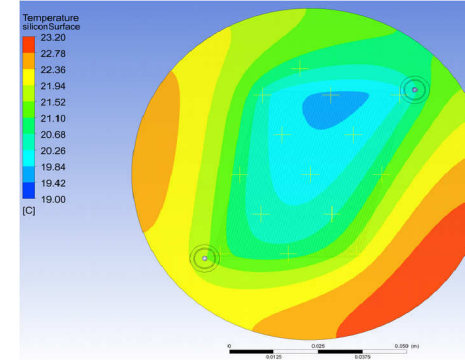
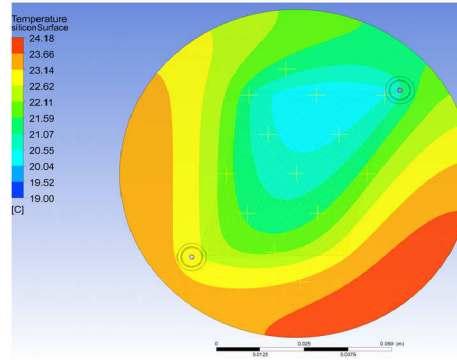
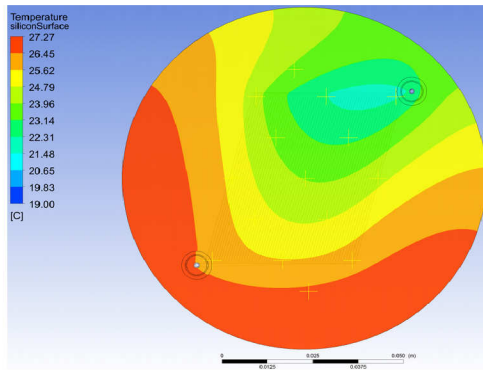
30 ml/min



50 ml/min

Heater set to 2.5 W

Simulation (without convection)

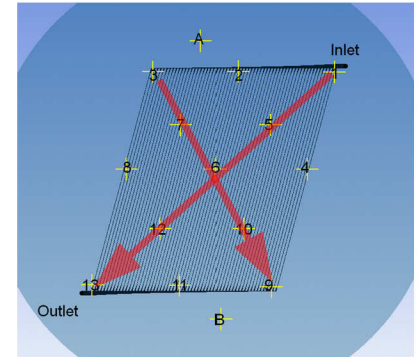
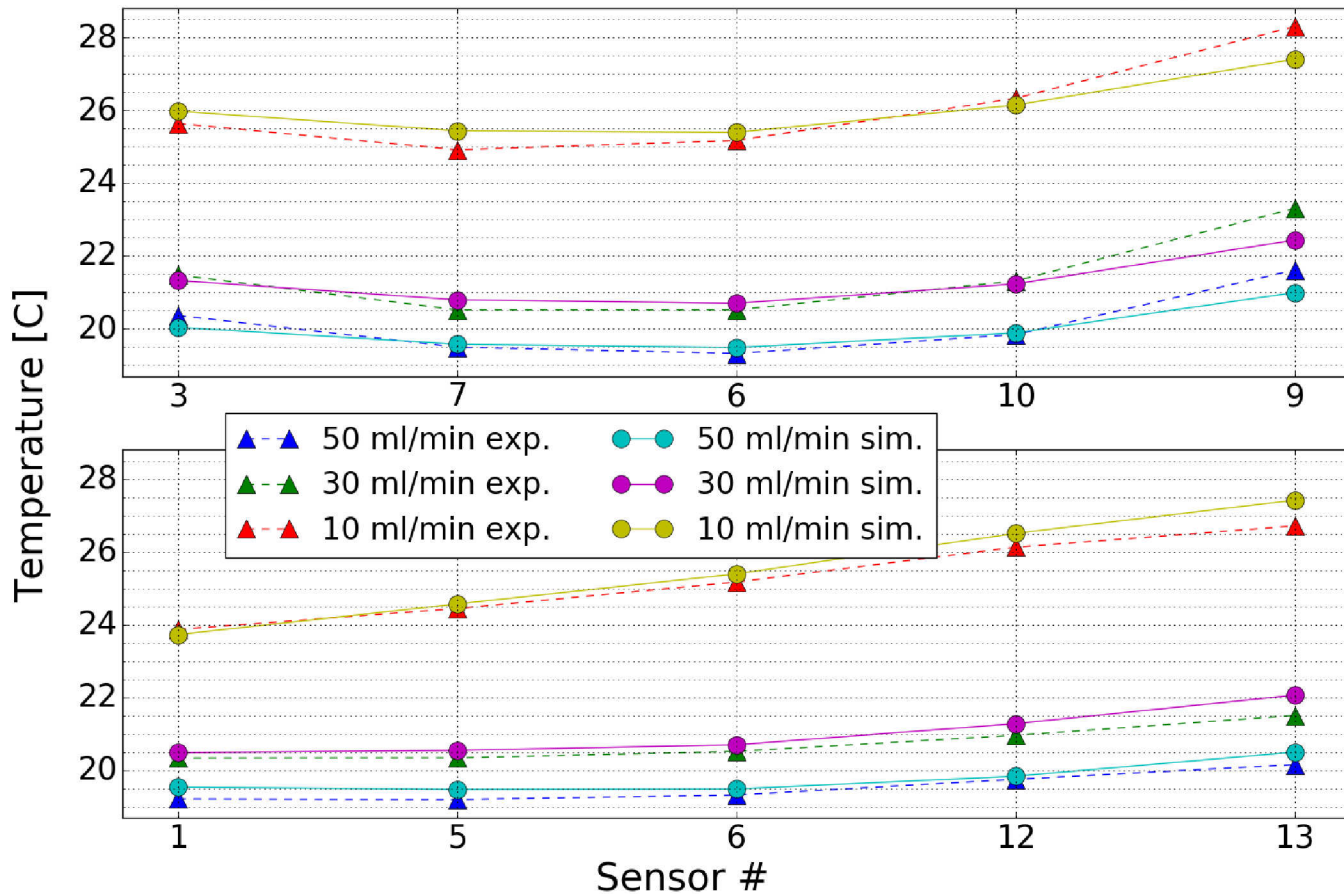


- Experiment and simulation in good agreement
- Actively cooled area has a gradient of below 4 °C

Fluid at ~19 °C

Temperature Along The Wafer Surface

Diagonals across the wafer with 2.5W on heater (in air)



- Values corrected for varying inlet temperature in the experiment
- Temperature sensors are calibrated to one reference sensor

Fluid at ~19 °C

- No hot-spots!
- Simulation in a good agreement with the experiment

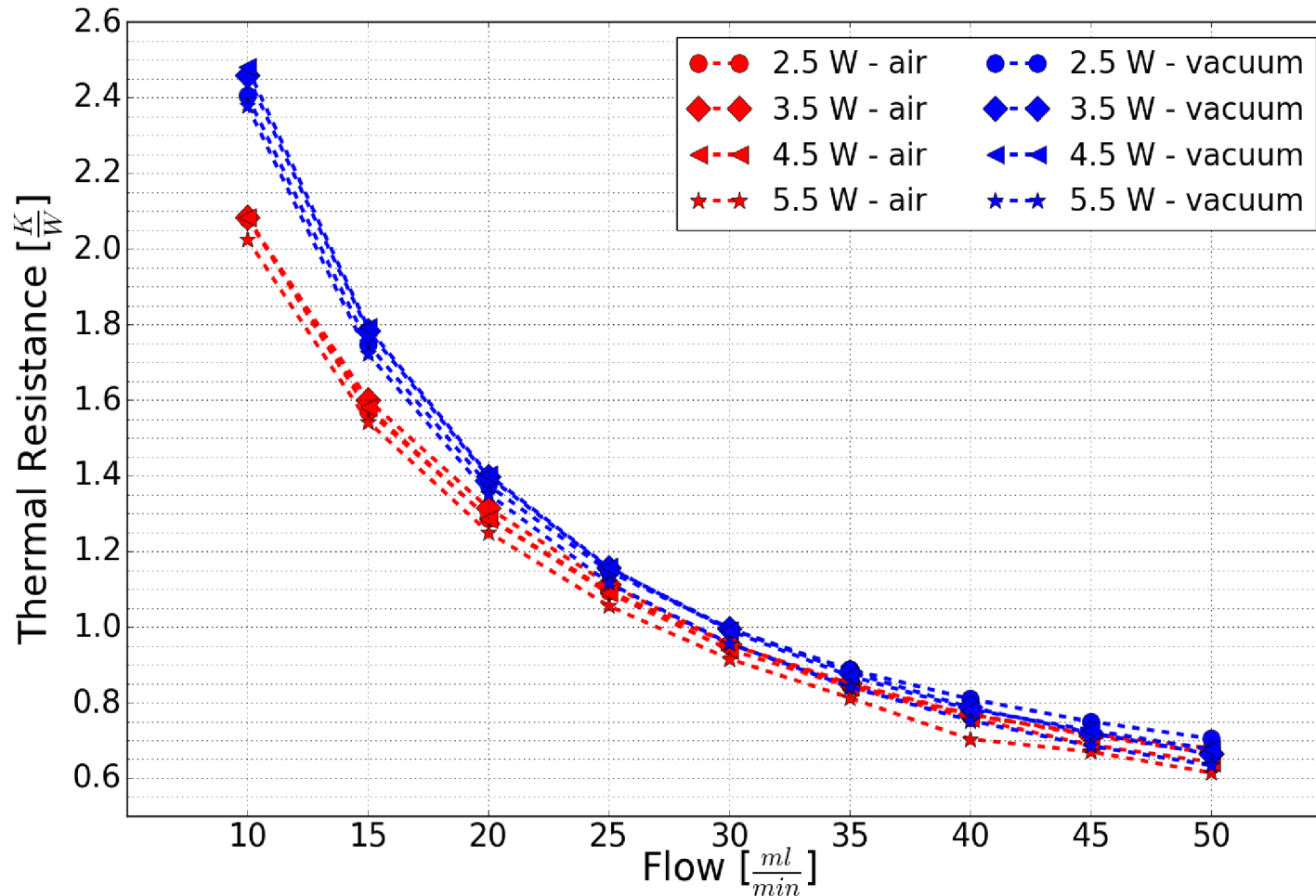
Maximum temperature difference below 4 °C between all sensors



Thermal Resistance

$$R = \frac{T_{outlet} - T_{inlet}}{P_{heater}}$$

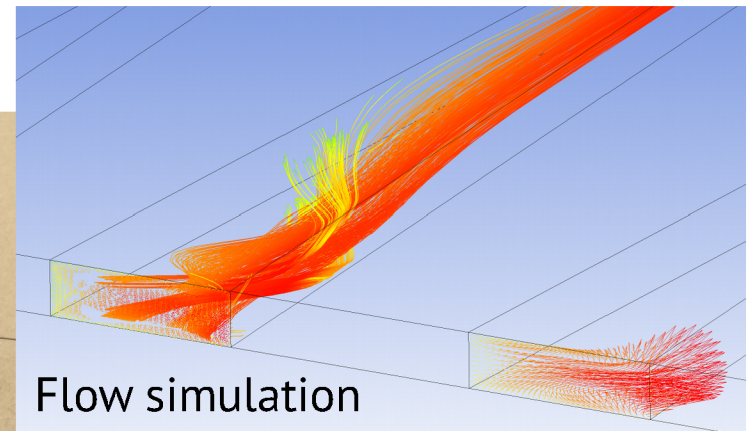
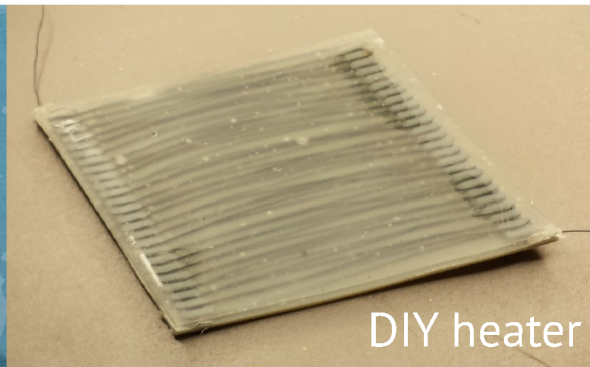
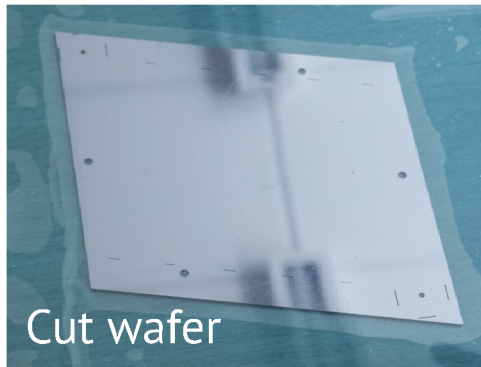
- Grouped in vacuum and air measurements
- The effect of convection is visible



Summary & Future Steps

- A micro-channel structure and a test stand was designed and produced
 - Flow and thermal tests show its general feasibility for large sensors
 - Volumetric flows up to 50 ml/min were tested and found to be able to keep the maximum temperature difference over the micro-channel structure below 4 °C
 - The simulation of the flow and the thermal properties is in a good agreement with the experiment
-

- Measurements with a wafer cut to the micro-channel structure dimensions
- Fluorescent spectroscopy flow measurements with fluorescent beads to compare with the simulation
- Paper under review!

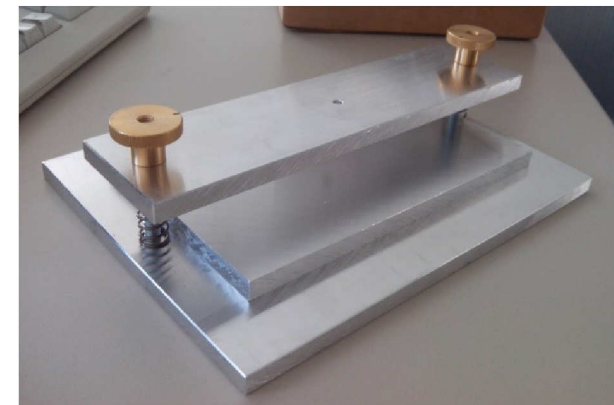
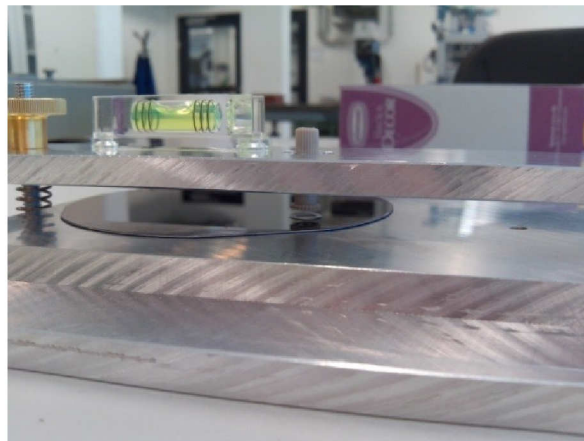
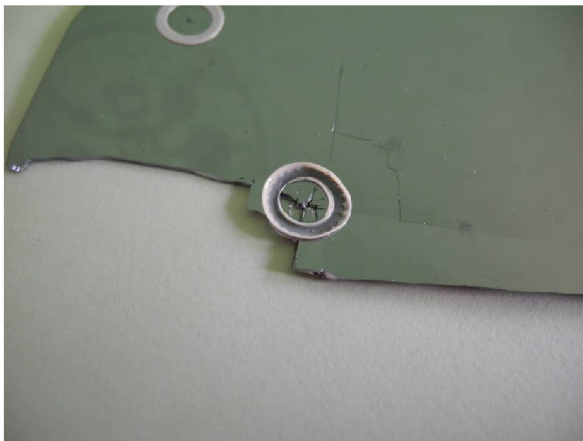
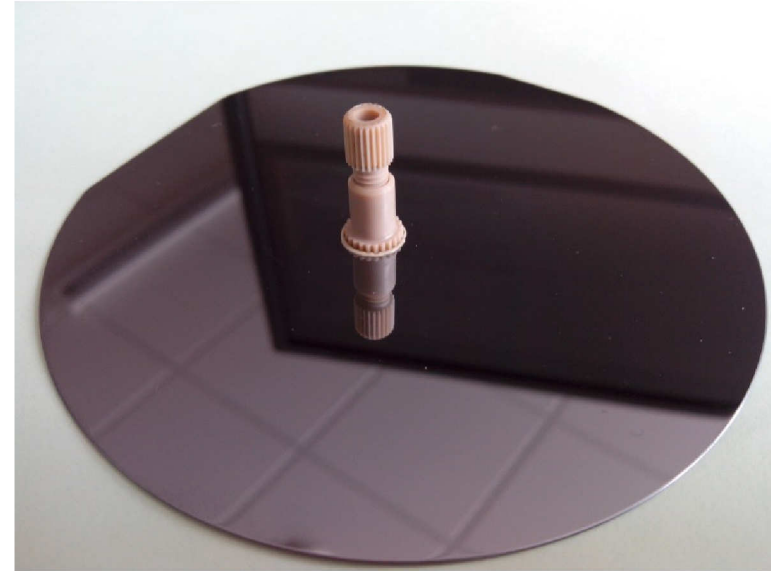


Thanks for your attention!



Putting The Sample Into The Setup

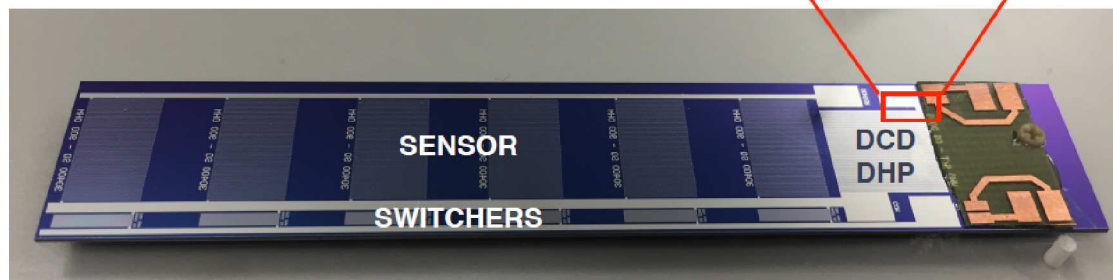
- NanoPorts are used to connect pipes to the micro-channels
- They are glued by heating up an adhesive ring between the NanoPorts and the silicon
- The NanoPorts are held in place by a self-made jig
- Pressure test showed that they can withstand pressures up to ~50 bar (tested on blank wafers)



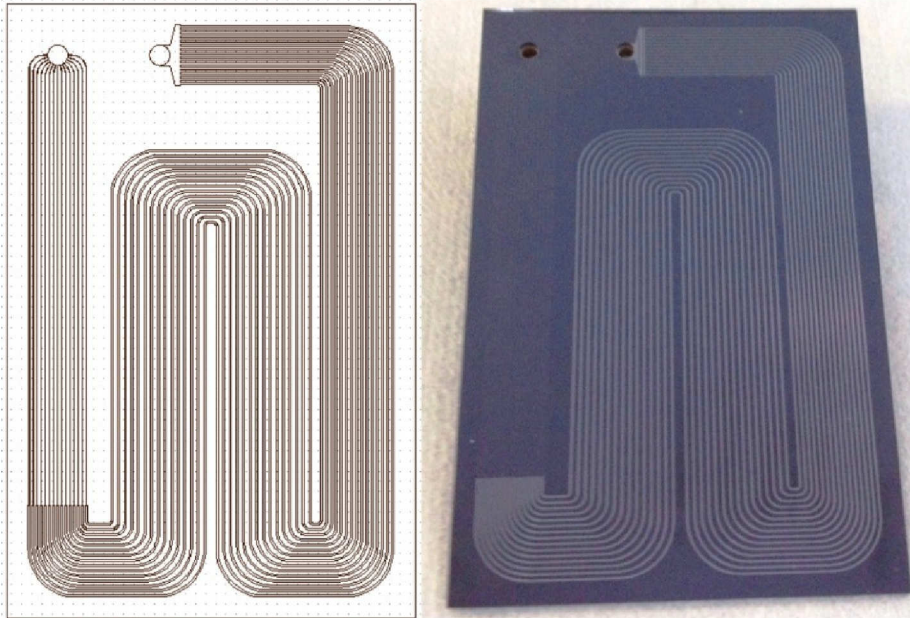
Other micro-channel projects

Working parameters

Element	R (Ω)	P (W)
Sensor	900	0.5
DCD	175	8
Switcher	250	0.5



- DEPFET ladder pixel detector for future colliders



- LHCb Velo

Laminar Or Turbulent

- Reynolds Number $Re = \frac{\rho v d_H}{\mu}$
 - d_H :hydraulic diameter
 - μ :kinematic viscosity
 - ρ :density
 - v :velocity
- Literature => Reynolds Number up to 1000 before transition
- Completely turbulent $Re > 3000$

Re	Flow [ml/min]
27	5
219	40
383	70
547	100

- With $d_H = 100 \mu\text{m}$
- With d_H set to maximal value $Re(100 \text{ ml/min}) = 995$



Manifold Shape

- We want a homogeneous flow along all channels
- Same pressure at each channel coming off the manifolds

$$\Delta p_n = \Delta p_{n+1}$$

- Pressure and flow can be derived from the Navier-Stokes equation

$$Q = \frac{\pi a^4}{8\eta L}$$

Q : flow

a : characteristic length (hydraulic diameter)

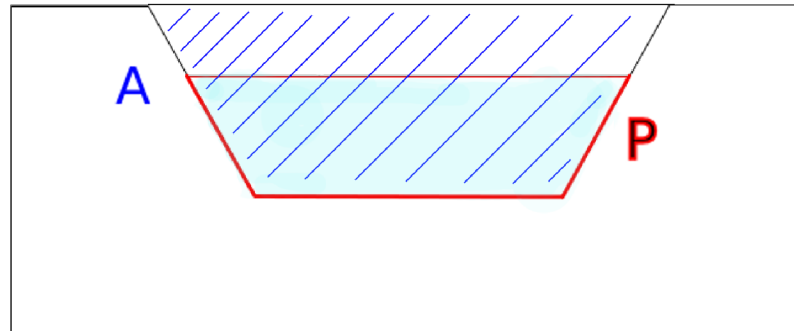
L : channel length

η : viscosity

$$d_H = \frac{4A}{P}$$

A : Area of channel cross section

P : wetted perimeter (circumference)



- Which results in a manifold-width as a function of channel number n

$$w_m(n) = \frac{h \left(\frac{w^4 h^4 (N-n)}{(w+h)^4 * N} \right)^{1/4}}{h - \left(\frac{w^4 * h^4 * (N-n)}{(w+h)^4 * N} \right)^{1/4}}$$

h : channel height
 w : channel width

